

(19)
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(A)(51) 。 Int. Cl. ⁷
H05B 33/22(11)
(43)2003 - 0011657
2003 02 11(21) 10 - 2002 - 0044612
(22) 2002 07 29

(30) JP - P - 2001 - 00230414 2001 07 30 (JP)

(71) 가 가
5 7 1(72) ,
5 7 1 가 가
,
5 7 1 가 가
가 ,
5 7 1 가 가

(74)

:

(54)

, 1 2 , 1

1.65 1

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6

, , , , .

1 .

2 EL .

3 EL .

4 EL .

5 EL .

6 1 .

7 6 .

8 2 .

9 3 .

10 4 .

11 10 , .

12 5 .

13 6 .

14 .

< >

1: , 2: 1 , 3: , 4: , 5: , 6: 2 , 7: (, 7': , 8: 2 , 9 가 , 10: 3 , 11: , 1

2: (3, 4, 5), 13: TFT (), 14: , 15: .

, , ()
)
 (" EL ") , 가 ,
 (Eastman Kodak Co.) C.W. Tang EL
 (C.W.Tang, S.A.VanSlyke, Applied Physics Letters, 51 , 913 , 1987) ,
 EL 가 .
 , (8 -) ,
 EL , (, (,
) (exciton) ,
 .
 EL 3 , () 2 , () ,
 가 ,
 .
 EL ,
 가 , 25% .
 , EL , () ()
 , 20% , 1.6 ,
 5% (Tetsuo Tsutsui " , , 1 , 3
 , 11 , 1995 9). EL ()
 EL) ()
 , EL
 63 - 314795 , ()
 , 가 .
 , 62 - 172691 ,
 , , 가 ,
 , () EL
 () EL
 .
 , 2000 - 323272 , EL
 ,
 EL , ,
 ,

· , EL () ,
(, EL ()) 가 .

(black mask) , 11 - 8070 , EL ,
가 , .

· , EL 11 - 8070 , ()
· , , EL
가 .

· , EL .

1 ,
1 2 , 1
가 .

· 1.65 .

2 1 ,

1 h 1 ,

< 1 >

$$h \geq H \cdot 4t / (1 + 3t)$$

·

t d/D ,

D ,

d ,

H .

3 1 , 1 ,

4 3 ,

1 h 1 ,

< 1 >

$$h \geq H \cdot 4t / (1 + 3t)$$

,

t d/D ,

D ,

d ,

H .

5 1 ,

1 1 , 1.65
2 .

6 5 , 2 1 .

7 5 , 1 2 .

8 7 , 1 2 가 가 .

9 8 , 가 H₂O () 가 .

3 10 가 8 , 가 1 , 1.65 .

11 1 , .

12 11 , (work function)가 4.3 eV .

13 11 , 1 .

14 13 , 가 4.3 eV .

15 ,

1 ,

1 2 ,

1 2 가
1 ,

1 2 ,

,

,

,

가 .

16 15 , (comb)
, 1 .

17 15 ,
, 1 .

18 29 , 15, 16 17 , 2 5
가 .

30 43 ,

1 14 가 . 1.65
, 2 3 ,
, 2 3 .

44 ,

1 ,

1 2 ,

1 2 가
30 ,

1 2 ,

,

,

,

가 .

45 44 ,
, 1 .

가 .

< >

EL 1.65

EL ()

가

EL (EL

1.65)

가

EL 20% 2 2

EL 80%가 1 1.65

EL

가

가

EL

1.65 EL

EL ()

EL 가

1

(

) 1 , " D" 1 EL ()
 , " d" EL ()
 . d D " t" (t = d/D) . " h" (1
) " H" (1) ,
 () (,) .

(,), D d ,

$$\frac{2Hd}{h} \leq \frac{D-d}{2} + 2d$$

h H 4 t/(1+ 3 t) .

가 , (-)
 가 ,
 가 . EL
 가 ,

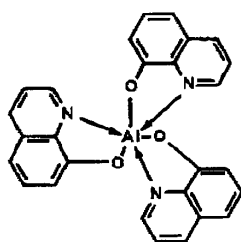
, .

, 1 2 1
 . 2 5 1 , 2 , EL .

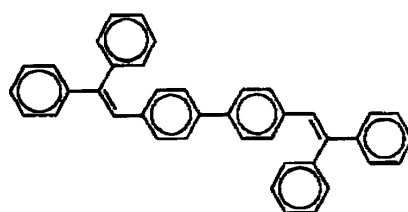
2 , 1, 1 () 2, 4, 2 () 6
 . 3 , 1, 1 2, 3, 1, 1
 4, 5 2 6 . 4 ,
 2, 3, 4 2 6 5 ,
 1, 1 2, 4, 5 2 6 .

, , , , ,
 , (, , , , ,
) , () ()
 , (, , , , ,
 -p-) .

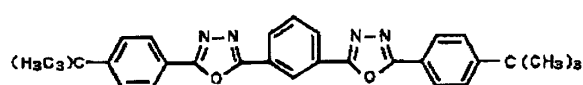
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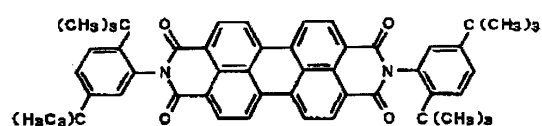
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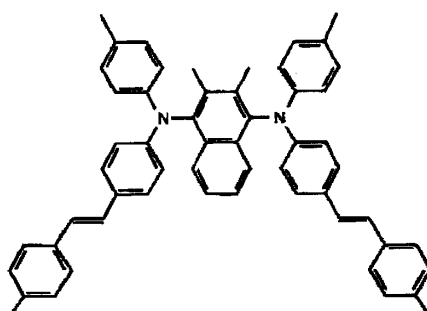
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4



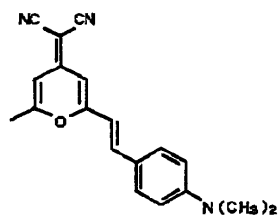
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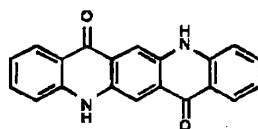
, (8 -) (Alq3) [1], () (BDPVBi) [2], 1,3 - (p - t - - 1,3,4 -) (OXD - 7) [3], N,N' - (2,5 - - t -) - 3,4,9,10 - (BPPC) [4], 1,4 - (N - p - - N - 4 - (4 -) [5]

가

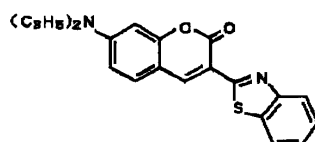
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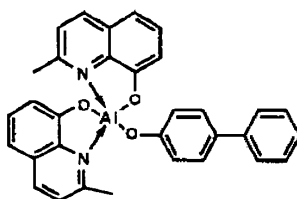
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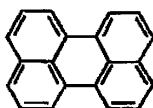
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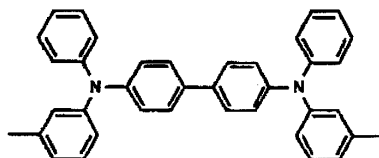
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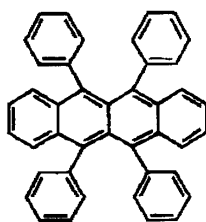
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11

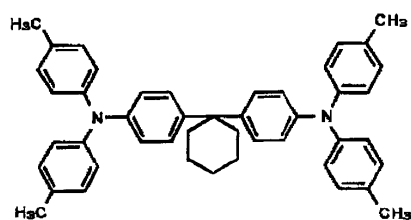


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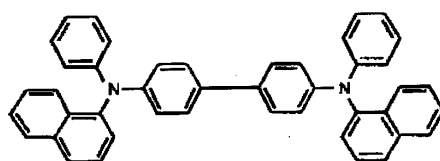


, - (Alq3 [1]) , 4 - - 2 - - 6 - (p -
) - 4H - (DCM) [6], 2,3 - [7] , 3 - (2' -
) - 7 - [8]
 (2 - - 8 -) - 4 - [9] [10]
 , 4,4' - (m -) (TPD) [11] , [12]

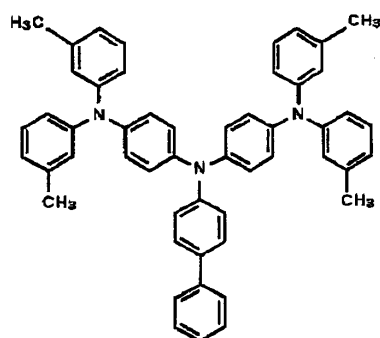
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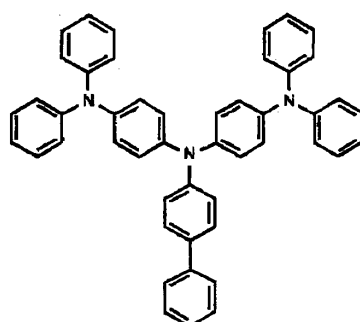
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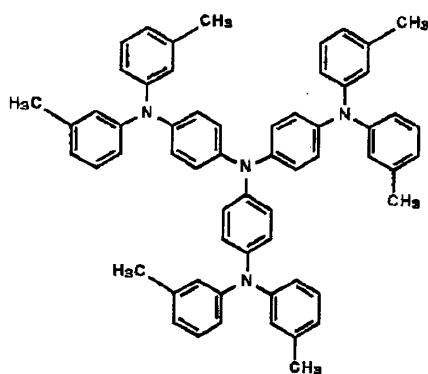
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16

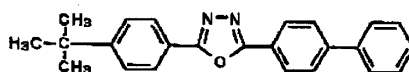


17

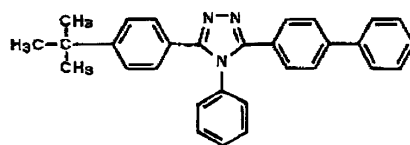


, (p -) - 1,1 - [13], TPD [11] N,N' - - N,N' -
 (1 -) - 1,1' -) - 4,4' - (NPB) [14]
 burst type) ([15] [17]) (star -

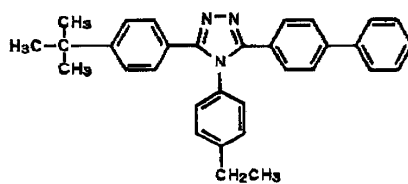
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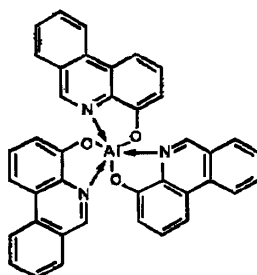
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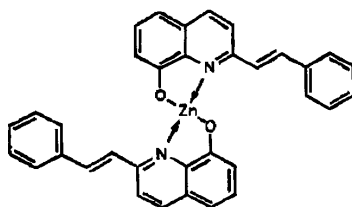
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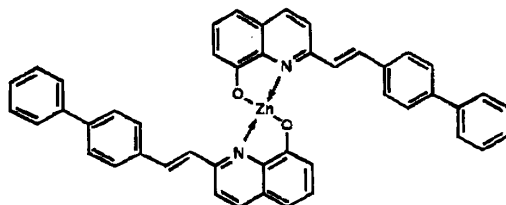
21



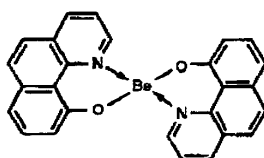
22



23



24



3] , 2 - (4 -) - 5 - (4 - t -) - 1,3,4 - (Bu - PBD) [18] OXD - 7 [1], [9], [21] [24] ([19], [20]), - ([1], [24]) .

mirror)

< 1>

$$h \geq H \cdot 4t / (1 + 3t)$$

,

 $t \propto d/D$

D

$$H = (\quad , \quad 1 \quad)$$

1. 가 , 1 가 . , 1 ,

EL, ()가 EL, () 1
EL, (,) EL 가 .

Figure 1: Energy level diagram of the GaN/AlN heterostructure. The diagram shows the conduction band (CB) and valence band (VB) of GaN and AlN. The GaN band gap is 3.4 eV, and the AlN band gap is 6.2 eV. The conduction band offset is 4.3 eV. The valence band offset is 1.8 eV. The diagram is labeled with 'GaN' and 'AlN' and shows the relative positions of the bands.

< 1>

1 6 7 6 1 ,
 2 6 12 7 6 ,
 $-$ $($ 7 $)$ $($ 7 $)$,
 $200 \mu\text{m}$ 7 , $a_1 = 1$
 $90 \mu\text{m}$, $a_2 = 90 \mu\text{m}$, $a_3 = a_4 = 100 \mu\text{m}$, $a_5 = 480 \mu\text{m}$.

1, PES 1 (roughening) 500 μm 11 ,
 1 1 ()
 7 20 $\Omega/\square$, ITO (80 μm , 120 μm) 1 2 .

[14] 3 20 nm ,
 [1] 4 50 nm .
 [18] 5 20 nm . 6
 7 , 3, 4, 5 " 12" .

(mask) 가 200 nm 2
 6 2 6 , 7 (teeth) (: 80 μm ,
 : 120 μm) 1 2 1
 10 V 가 , 14,000 cd/m^2 .

< 2>

8 2 , 2 6 12
 . 2 , 1
 PES (: 100 μm) 1 가 9 SiO_2 가 200 nm 2 ,
 1 1 1 , 가 9가
 . 10 V 가 , 13,000 cd/m^2 .

< 3>

9 3 , 2 6 12
 . 3 , 2 2 8 80 μm , PES
 3 10 (: 18 μm) 2 8 가 9 ,
 3 1 . 2
 가 , 13,700 cd/m^2 . 10 V .

< 4>

10 4 , 2 6 12
 . 4 , 1
 . () 7'
 200 μm 7' . 7' 11
 . 7' , a1 = 190 μm , a2 = 90 μm , a3 = a4 = 100 μm , a5 = 480 μm .

1, PES , 가 500 μm
 1 1 11 ,

1, 7' 20 $\Omega/\square$ ITO (: 80 μm , : 120 μm) 1 2 .

[14] 가 20 nm 3
[1] 가 50 nm 4 .
[18] 가 20 nm 5 . 10
3, 4 5 " 12" .

가 200 nm 2 6
(: 80 μm , : 120 μm) 1 2
4 10 V
가 14,500 cd/m^2 .

< 5>

12 5 , 2 6 12
5 , 1
PES (: 100 μm) 1 가 9 SiO_2 가 200 nm 2
1 8 1 , 가 9가
V 4 5 . 10
가 12,900 cd/m^2 .

< 6>

13 6 , 2 6 12
6 , 5 2 8 80 μm , PE
S 3 10 (: 18 μm) 2 8 가 9 ,
3 10 1 5
6 . 10 V 가
13,500 cd/m^2 .

() , (EL) 14 TFT (),
14 15 .

14 가 20 가 , 15 가 ,
15 가 , 14 21 가 ,
14 가 , TFT 13 가 ,
가 (EL 12) .

가 ,
. 가 20 21 , ,
가 ,
() .

EL
.

EL

(57)

1.

1

2

1

1.65

2.

1

1

h가

1

< 1 >

$$h \geq H \cdot 4t / (1 + 3t)$$

t d/D

D

d

H

3.

1

1

4.

3

1

h가

1

< 1 >

$$h \geq H \cdot 4t / (1 + 3t)$$

,

t d/D ,

D ,

d ,

H .

5.

1 , 1 1 , 1.65
2 .

6.

5 , 2 1 .

7.

5 , 1 2 .

8.

7 , 1 2 가 가 .

9.

8 , 가 H₂O () 가 .

10.

8 , 가 1 , 1.65 3 가 .

11.

1 , .

12.

11 , (work function)가 4.3 eV .

13.

11 , 1 .

14.

13 , 가 4.3 eV .

15.

1 ,

1 2 ,

1 2 가
1 ,

1 2 ,

,

,

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16.

15 , (comb) ,
1 .

17.

15 , ,
1 .

18.

1 ,

1 2 ,

1 2 가
2 ,

1 2 ,

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19.

18 ,
1 .

20.

18 ,
1 .

21.

1 ,
1 2 ,
1 2 가
3 ,
1 2 ,
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22.

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1 .

23.

21 ,
1 .

24.

1 ,
1 2 ,
1 2 가
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25.

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27.

1
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28.

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29.

27
1
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30.

1
2
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1

31.

30 , 1 h가 1 ,

< 1 >

$$h \geq H \cdot 4t / (1 + 3t)$$

t d/D ,

D ,

d ,

H .

32.

30 , 1 ,

33.

32 , 1 h가 1 ,

< 1 >

$$h \geq H \cdot 4t / (1 + 3t)$$

t d/D ,

D ,

d ,

H .

34.

30 , 1 , 2

35.

34 , 2 1 .

36.

34 , 1 2 .

37.

36 , 1 2 가 가 .

38.

37 , 가 H_2O () 가 .

39.

37 , 가 1 , 3
가 .

40.

30 , .

41.

40 , 가 4.3 eV .

42.

40 , 1 .

43.

42 , 가 4.3 eV .

44.

1 ,
1 2 ,
1 2 가
30 ,
1 2 ,
 ,

，

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45.

44
1 ，

46.

44
1 ，

47.

1 ，

1 2 ，

1 2 가
31 ，

1 2 ，
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48.

47
1 ，

49.

47
1 ，

50.

1 ，

1 2 ，

1 2 가
32 ，

1 2 ,

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51.

50 ,

1 .

52.

50 ,

1 .

53.

1 ,

1 2 ,

1 2 가
33 ,

1 2 ,

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54.

53 ,

1 .

55.

53 ,

1 .

56.

1 ,

1 2 ,

1 2 가
34 ,

1 2 ,

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57.

56 ,

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1 .

58.

56 ,

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1 .

59.

1 2 ,

1

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1.65

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1

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60.

1 ,

1 2 ,

1 2 가
59 ,

1 2 ,

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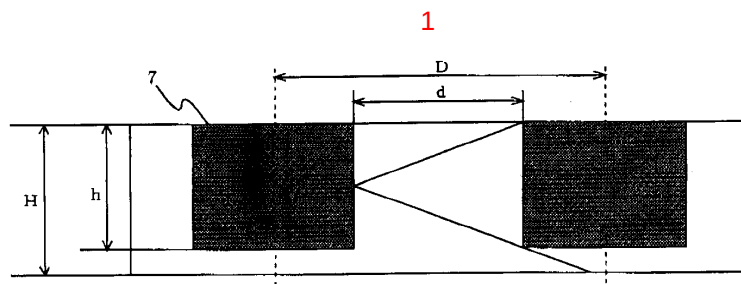
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61.

1 2 , 1
,
, 1

62.

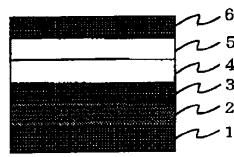
1 ,
1 2 ,
1 2 가
61 ,
1 2 ,



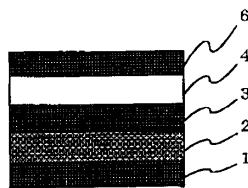
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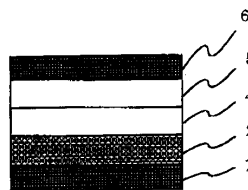
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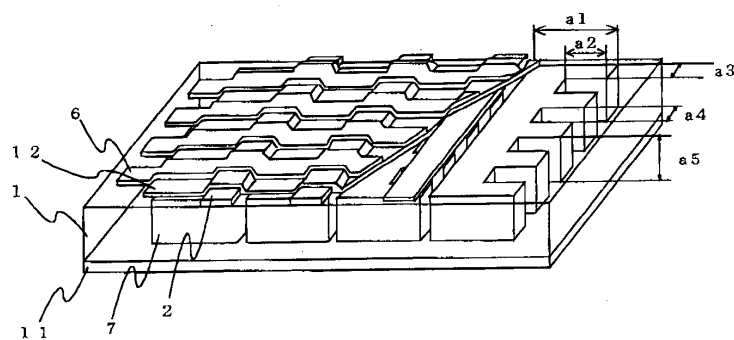
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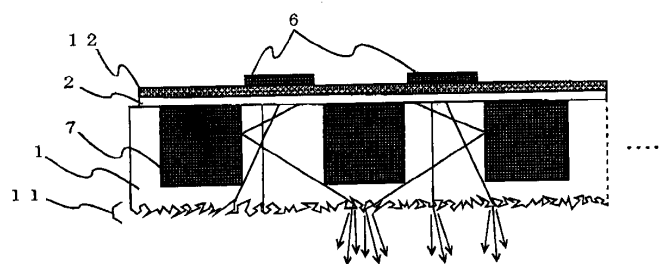
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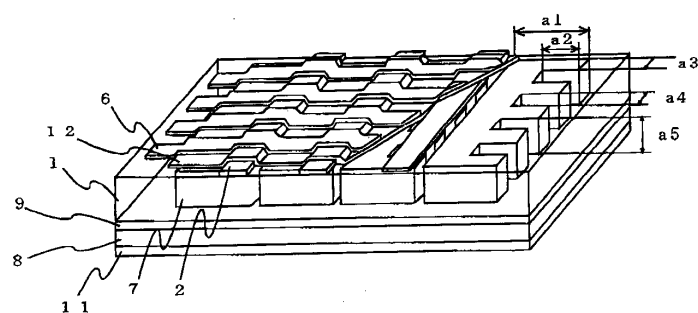
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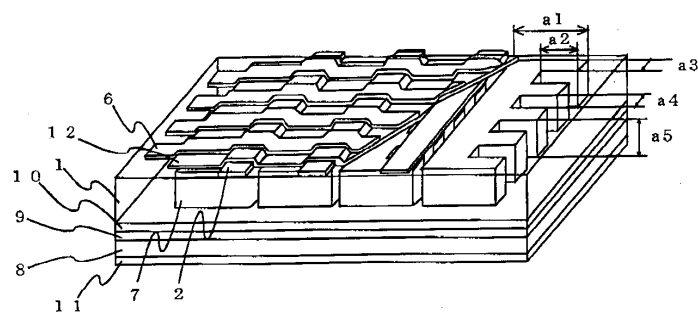
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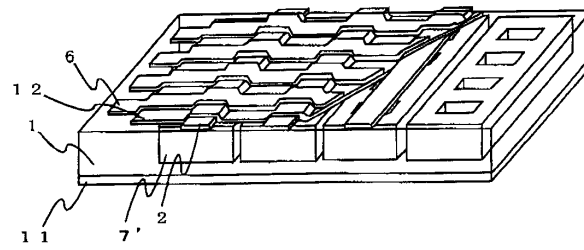
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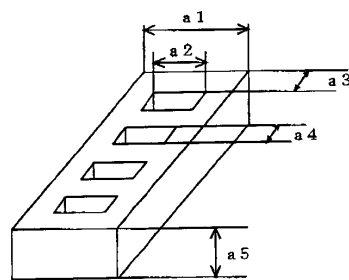
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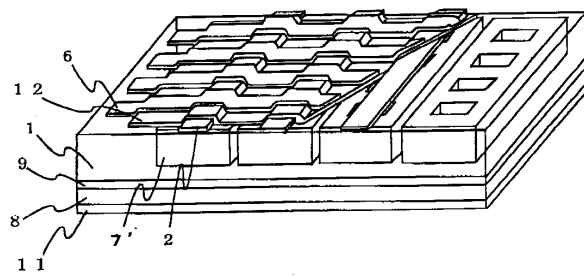
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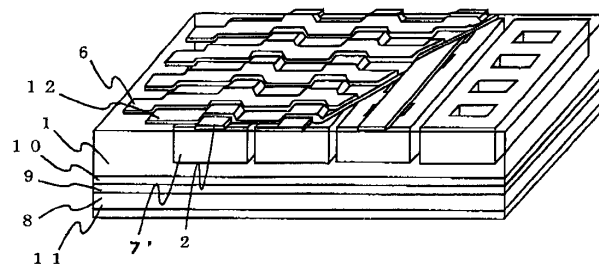
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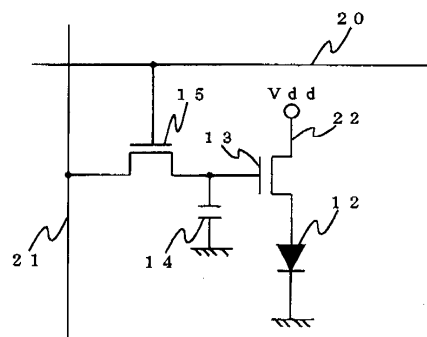
12



13



14



专利名称(译)	使用电灯发光装置的发光元件和显示装置，没有光泄漏和改善的光源		
公开(公告)号	KR1020030011657A	公开(公告)日	2003-02-11
申请号	KR1020020044612	申请日	2002-07-29
申请(专利权)人(译)	三星SD眼有限公司		
当前申请(专利权)人(译)	三星SD眼有限公司		
[标]发明人	TOGUCHI SATORU 도구찌사토루 ODA ATSUSHI 오다아쯔시 ISHIKAWA HITOSHI 이시가와히토시		
发明人	도구찌,사토루 오다,아쯔시 이시가와,히토시		
IPC分类号	H05B33/02 H01L51/50 H05B33/22 H05B33/04 H01L51/52 H05B33/26 G09F9/30 G09F9/00 H01L27/32 G09G3/32		
CPC分类号	H01L51/5221 G09G2300/0842 H01L51/5281 H01L27/3244 H01L51/5268 H01L51/5237 H01L51/5271 G09G3/3225 H01L51/5231		
代理人(译)	PARK, 常树		
优先权	2001230414 2001-07-30 JP		
其他公开文献	KR100478525B1		
外部链接	Espacenet		

摘要(译)

本发明涉及配备有机电致发光器件的发光器件，所述有机电致发光器件由多于1个单元层的有机薄膜层组成，所述单元层至少包括在第一电极和安装在光学传输器上的透明第二电极之间允许的发光层。基质。并且此时，为了包括中断光传输基板从相应的有机电致发光器件发射到一个像素的装置，光通过反射制造装置的光进入光相邻的像素区域。它包括具有折射率的材料，其中光传输基板的折射率大于1.65或更大，或者包括发光层。在侧面的相对侧提供光漫射功能，其中为了防止光透射基板与第一电极接触的全反射。通过这种配置，可以制造其中没有光泄漏并且具有优异的光学提取效率的发光器件。因此，可以制造高强度低压操作显示装置。光传输基板，有机电致发光器件，全反射，光学提取，光泄漏。

